

Title (en)

METHOD AND APPARATUS FOR SUBSTRATE BIASING IN MULTIPLE ELECTRODE SPUTTERING SYSTEMS

Title (de)

VERFAHREN UND VORRICHTUNG ZUR POLARISATION VON SUBSTRAT IN MEHRFACHELEKTRODEN-SPUTTERING-SYSTEMEN

Title (fr)

TECHNIQUE ET DISPOSITIF DE POLARISATION DU SUBSTRAT DANS DES SYSTEMES DE PULVERISATION A ELECTRODES IN MULTIPLES

Publication

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Application

**EP 00970916 A 20001013**

Priority

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Abstract (en)

[origin: WO0129278A1] A method and an apparatus are disclosed for causing ion bombardment of the substrate (3) during sputter deposition of an insulating or conducting material on a substrate (3) when using dual cathode (9, 10) or dual anode sputtering approaches. A novel electrical circuit including a center-tapped transformer (17) is disclosed to permit a controllable potential to be applied to the substrate (3) relative to the plasma potential, without the necessity of an additional power supply. Also disclosed are approaches which permit the use of an biasing supply (19 or 20), either dc or high frequency ac, and which can permit continuous discharging of the surface through alternate ion and electron bombardment.

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Citation (search report)

- [X] US 5082546 A 19920121 - SZCZYRBOWSKI JOACHIM [DE], et al
- [X] EP 0908535 A1 19990414 - COCKERILL RECH & DEV [BE]
- See references of WO 0129278A1

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